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Compounds of Fluorine

1 Compounds of Fluorine with Noble Gases

Compounds of fluorine with noble gases are covered in "Edelgasverbindungen" Erg.-Werk, Bd. 1, 1970.

2 Compounds of Fluorine with Hydrogen

2.1 Hydrogen Fluoride HF (and its isotopic species)

2.1.1 Preparation, Handling, Uses

For formation of HF see the chapter on the gas-phase reactions of fluorine with hydrogen in "Fluorine" Suppl. Vol. 2, 1980, as well as Chapter 2.1.8 in this volume. For formation of hydrofluoric acid see also p. 246.

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2.1.1.1 Laboratory Preparation, Dehydration, and Purification

2.1.1.1.1 Preparation

The laboratory preparation of HF is rarely undertaken because HF is available in generally sufficient purity from commercial sources (see p. 5). Procedures for preparing high-purity HF from commercial HF are given below.

Anhydrous HF can be prepared by thermal decomposition of dry KHF₂ at 500°C in a noble metal apparatus followed by distillation of the hydrogen fluoride [1], see also "Fluor" Erg.-Bd. 1, 1959, p. 144. It is important to use dried KHF₂ if low-conductivity, i.e., water-free, HF is required. The salt is dried by electrolytic methods [2], by heating in fluorine at 150°C [1], or by heating in vacuo up to 200°C for ten hours or more [3].

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Instead of the potassium salt, the nonhygroscopic and thermally less stable sodium salt, NaHF₂, can be used as the source of HF [4]. The hydrogen fluoride formed by decomposition of NaHF₂ (15 min at 350°C, final temperature 450°C) was fractionated in a fluorothene distillation assembly to give samples with electrical conductivities as low as $1.6 \times 10^{-6} \Omega^{-1} \cdot \text{cm}^{-1}$ [4], see also [5].

A generator for use in HF adsorption studies based on the temperature-dependent dissociation of NaHF₂ is described in [6]. NaHF₂ gives HF pressures of 0.001 to 0.3 Torr at 60 to 135°C. This generator allows a dry carrier gas (N₂) to pass through the thermoregulated chamber filled with crystalline NaHF₂ to yield HF concentrations of 5 to 1000 ppm at flow rates \leq 5 L/min for periods up to one year [6].

References:

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2.1.1.1.2 Dehydration. Determination of Traces of H₂O

A great number of methods have been proposed in recent years for the dehydration of HF. The best seems to be the addition of $SOCl_2$ [1, 2, 3] since the reaction products (SOF_2 , HCI, and SO_2) are all gases and can be easily removed. An additional distillation is also useful.

The treatment of hydrogen fluoride containing small amounts of water with desiccants such as CoF₃ [4, 5], CoF₃ and NaF [6], VF₅ [3], and ClF₃ [3] has been recommended. The opinions on the usefulness of elemental fluorine as a desiccant differ. According to [7] hydrogen fluoride used in conductance work can be dried by elemental fluorine. Kwasnik [2] recommends introduction over 30 min directly into the cooled HF product. On the other hand, attempts to prepare anhydrous hydrogen fluoride by bubbling fluorine through the acid [3] were reported to be unsuccessful.

The procedure of continuously drying hydrogen fluoride by electrolysis has been suggested several times [8, 9, 10]. The addition of other electrolytes, usually KF, enables the electrolysis to be continued until the water content has been reduced even further. However, the rates of discharge of O_2 and OF_2 are much lower than the rate of discharge of fluorine, and thus large quantities of fluorine must be released before dry HF is obtained [11]. The current reversal technique [12] leads to more effective drying on account of extensive anodic depolarization. A further advantage is that the high average current reduces the time required for drying and thus markedly reduces the attack on the Ni electrode [12]. Also see the chapter on purification on p. 4.

The water content in HF is determined by titration using the Karl Fischer reagent [13] and by conductance measurements. The direct determination of H_2O in the acid by titration is based on the reaction $I_2 + SO_2 + 2H_2O = 2HI + H_2SO_4$. Anhydrous CH_3OH and pyridine are used for the solvation of iodine and SO_2 . The methods used for the fixation of the hydrogen fluoride vary; for example, cyclohexene and KHF₂ [14] have been used for

this purpose. Aqueous HF can be titrated directly, see [15]. The determination of traces of water in hydrogen fluoride by the Karl Fischer reagent is described in [16].

Since the titration does not give the required accuracy over the range from zero to a few tenths of a percent of H_2O [17], many attempts have been made to determine the H_2O content in HF on the basis of the electrical conductivity, for example [18, 19]. The conductivity of liquid hydrogen fluoride is changed to almost the same extent by moisture and H_2SO_4 . The presence of other impurities has no appreciable effect on the electrical conductivity [17]. For extremely pure hydrogen fluoride a limiting value of the electrical conductivity of $1.0 \times 10^{-6} \, \Omega^{-1} \, \mathrm{cm}^{-1}$ is assumed, see p. 101. The investigations made by Wejnar [20] show the effect of SO_2 on the conductivity of wet HF (up to 1.5% H_2O) in continuous HF production [20]. Conductivity measurements give the relation between the H_2O content a (in wt%) of hydrogen fluoride and the specific resistance R (in $\Omega \cdot \mathrm{cm}$) at $-15^{\circ}\mathrm{C}$ [7]: $\log a = 1.808 - 1.528 \, \log \, R_{-15}$. The effect of temperature on R is represented by $R_1 = R_{-15} \cdot (0.9307 - 4.02 \times 10^{-3} \mathrm{t} + 1.01 \times 10^{-4} \mathrm{t}^2)$ for t = -50 to $+10^{\circ}\mathrm{C}$ [7], see also [11].

There are few reliable measurements of the conductivity of H_2O in HF. Engelbrecht and Nachbaur [21] studied the system H_2O -HF between 20 to 90% HF at 0°C, and Fredenhagen, Cadenbach [22] have investigated this system at -15°C. The results obtained by [22] are in good agreement with the values calculated by [11, pp. 213/4] from the equations (given above) of [7]. More information is given in Chapter 2.1.13.7.

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2.1.1.1.3 Purification on the Laboratory Scale

The methods employed in purifying commercial grade HF are distillation (fractional, repeated, isothermal, and sub-boiling distillation) and filtering. The aim is to remove very small amounts of Si, As, Sb, Fe, heavy metals, organic matter, etc. from commercial grade HF to yield high-purity HF. (The dehydration is described separately on p. 2.)

In earlier distillation work, container materials used were platinum, silver, copper, and sometimes quartz. Nowadays, these materials have been replaced by plastics, such as polyvinyl chloride, polyethylene, and teflon (see also p. 20). The distillation rates are frequently very low (centiliters per day to centiliters per hour) and differ from method to method. Some additives are included in the various processes: BaCO₃ or Ba(OH)₂ (to remove SO₂ and H₂SO₄) [1], Ag₂CO₃ (to remove CI⁻) [1], H₂O₂ and Ba(OH)₂ [2], KMnO₄ and mannitol [3, 4] (for oxidizing and complexing metal impurities), and NaF (for H₂SiF₆ removal) [5].

Filtering. Tilton et al. [6] describe a method which consists of passing gaseous HF through a filter of fine teflon shavings and a teflon bubbler into triple-distilled H_2O in an ice-cooled platinum vessel [6]. A polyethylene apparatus in which HF gas is carried in N_2 through polyethylene beads and a solution of NaF (to remove H_2SiF_6) and then into H_2O distilled in a polyethylene still is described in [5]. The resulting 50% acid contains $> 1 \mu g$ Cu, $> 1 \mu g$ Fe, and $5 \mu g$ Si per mL acid [5]. Ultrapure 50% hydrofluoric acid containing 2 ppb/mL K and 0.08 ppb/mL Pb needed in analytical work (returned lunar samples) was produced by [7]. HF gas passes a teflon filter and is then frozen by cooling with liquid N_2 . After distillation the gas is introduced into very pure H_2O [7]. Gaseous HF is also purified by passing through an active-carbon filter [4] or a fine filter made of polychloroethylene [3]. After absorption in H_2O (specific resistance 10×10^6 to $15 \times 10^6 \Omega$ cm [3]) the aqueous HF is distilled. Treatment with mannitol and KMnO₄ [3, 4] is also included in this method.

Fractionation. The distillation columns described in [8] and [9] are similar. They are suitable for fractionation of commercial grade hydrogen fluoride to obtain an anhydrous product. The distillate is taken off in the liquid phase from the vicinity where the Pt condenser is cooled to -40° C to yield some 120 mL/day. The conductivity of the product was on the order of $10^{-6} \Omega^{-1} \cdot \text{cm}^{-1}$ at 25°C [9].

Repeated Distillation. Very pure hydrogen fluoride (e.g., <1 μ g Pb/g) is obtained by distilling 100% HF at room temperature from a feed bottle into a dry-ice cooled collection bottle five times (polyethylene still, total distillation time of 10 h). The advantage of this method is the preparation of pure HF solutions of any desired strength by carefully mixing the hydrogen fluoride with high-purity triple-distilled H₂O [10].

Isothermal Distillation. This method developed by [13] and used by [2, 11, 12] is simply the molecular diffusion of gaseous HF from commercial HF into deionized $\rm H_2O$ at constant temperature, usually 18 to 25°C. Polyvinyl chloride [2] and polyethylene [11, 12] stills are suitable. Disadvantages: length of the procedure on account of the low transfer rates and the quality of the acid obtained, which depends on the quality of the $\rm H_2O$ used for absorption. Advantage: simple room-temperature method.

Sub-boiling Distillation. This method [14] involves a slow sub-boiling evaporation at temperatures (70 to 85° C [14]) well below the boiling point of the azeotropic mixture HF/H₂O (111.4°C, see p. 240). This method was improved in [15, 16]. The feed acid used was 48% [14 to 16]. Stills were made of polyethylene [14] and teflon [15, 16]. Disadvantage of this method: only up to 48% hydrofluoric acid can be obtained.

The effectiveness of a distillation of hydrofluoric acid (48%) as analyzed by spectro-
graphic methods [17] is shown in the following table (values in ppb) [16]:

element feed		product residue		element feed		produ	ct residue
ΑI	7	2	20	Mg	20	3	30
В	2	< 0.5	3	Mn	3	0.2	5
Ca	700	300	200	Ni	5	<1	20
Cr	3	<1	30	K	20	<5	30
Со	3	<1	7	√Na	>1000	50	>1000
Cu	30	2	80	Sr	<10	<10	<10
Fe	30	2	100	Zn	50	<1	200
Pb	2	<1	2				

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2.1.1.2 Industrial Production

2.1.1.2.1 General Remarks

In the last 30 years the industrial production of nyurogen moride and hydrofluoric acid has increased considerably since HF is the most important starting material for fluorine chemistry (see Chapter 2.1.1.7, p. 22, on uses of HF). The consumption of HF in the western hemisphere has been reported as {1}:

1964	1970	1972	1980
555 000 t	960 000 t	1 045 000 t	1820000 t (estimated)

The total HF consumption in the USA increased from 205 000 t in 1965 to 316 000 t in 1979 [2], see also [3, 4].

A large number of publications, usually patents, are available on industrial production of HF. Selected publications are summarized in the following chapters to survey new developments.

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2.1.1.2.2 Manufacture from CaF₂

2.1.1.2.2.1 Manufacture from CaF2 and H2SO4

2.1.1.2.2.1.1 General Remarks

Hydrogen fluoride is almost always obtained by reacting acid-grade fluorspar (CaF₂) with H_2SO_4 : CaF₂ + H_2SO_4 \rightarrow 2HF + CaSO₄. This well-known process was described in "Fluor" Erg.-Bd. 1, 1959, p. 146. Acid-grade fluorspar is obtained as finely ground flotation product from crude fluorspar (CaF₂ content 50 to 90%) or as a synthetic product from H_2SiF_6 (see p. 15). Generally it has the following specifications:

CaF ₂	min. 97%	≈98%	min. 96.5 to 98%
SiO ₂	max. 1%	max. 1%	max. 1%
S	max. 0.01%	max. 0.03%	0.05%
CaCO ₃	_	max. 1%	principal impurity
moisture	-	max. 1%	max. 0.05%
flotation agent	0.03%	_	
Ref	[1]	[2]	[3]

The dried flotation spar is reacted with ca. 98% sulfuric acid (possibly with 20 or 65% oleum added) or with SO₃ and steam (see p. 7) [1]. Contamination of the fluorspar causes such side reactions as [1, 3, 4]: $SiO_2 + 2CaF_2 + 2H_2SO_4 \rightarrow SiF_4 + 2CaSO_4 + 2H_2O$; $SiO_2 + 4HF \rightarrow SiF_4 + 2H_2O$; $SiF_4 + 2HF \rightarrow H_2SiF_6$; $CaCO_3 + H_2SO_4 \rightarrow CaSO_4 + H_2O + CO_2$; $2H_2S + SO_2 \rightarrow 3S + 2H_2O$; $H_2SO_4 + H_2S \rightarrow S + SO_2 + 2H_2O$; $R_2O_3 + 3H_2SO_4 \rightarrow R_2(SO_4)_3 + 3H_2O$, where R = Fe, Al. These reactions lower the yield of HF and produce unwanted impurities [1, 3, 4].

The conversion of CaF_2 into HF is carried out in a heated rotating kiln made of low-silicon steel. The purity of the HF obtained is affected by the purity and fineness of the fluorspar, the concentration of the H_2SO_4 , the ratio CaF_2/H_2SO_4 (determined usually to assure the quality of the by-product $CaSO_4$), the temperature of the reaction, and the mixing efficiency [4], see also [1 to 3].

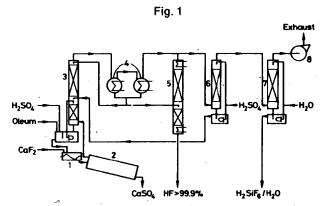
References:

[1] W. Schabacher (in: Ullmanns Encyclopädie der technischen Chemie, 4th Ed., Vol. 11, Weinheim/Bergstr. 1976, pp. 598/606). – [2] W. R. Rogers, K. Muller (Chem. Eng. Progr. 59 No. 5 [1963] 85/8). – [3] D. Candido, G. P. Mathur (Ind. Eng. Chem. Process Design Develop. 13 [1974] 20/6; C.A. 80 [1974] No. 52699). – [4] J. F. Gall (Kirk-Othmer Encycl. Chem. Technol. 3rd Ed. 10 [1980] 733/52, 742/4).

2.1.1.2.2.1.2 Industrial Processes

This chapter gives some examples for the manufacture of hydrogen fluoride in continuous operations. For processes developed before the middle fifties, see "Fluor" Erg.-Bd. 1, 1959, p. 156.

The Buss AG (Switzerland) [1 to 4] developed a process which has been used all over the world [5]. A flow sheet for this process is shown in **Fig.** 1 from [5]. Corrosion of the externally heated rotating kiln is considerably reduced by a special Ko-kneader [1 to 4], a continuous screw conveyor of corrosion-resistant alloy, before the kiln. About 30% of the mixture of CaF_2 and preheated H_2SO_4 react at 100 to 120°C in the Ko-kneader. The dust, water, and sulfur content of the crude gas is retained in the pre-wash system. Oleum in the column sump binds the used wash water. The pre-purified gas is liquefied in two condensors to form low-moisture, pre-purified HF, which can be further purified by distillation to ca. 99.9% HF [6].

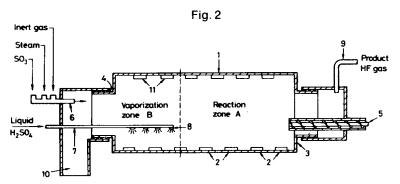


Manufacture of hydrogen fluoride, Buss AG (Switzerland) [5].

- 1) Ko-kneader. 2) Rotary kiln. 3) Pre-wash system. -
- 4) Condensors. 5) Distillation column. -
- 6) H₂SO₄ absorption tower. 7) H₂O absorption tower. -
- 8) Exhaust.

The corrosion of the rotary kiln can be also reduced by an Allied Chemical Corp. process [7], in which a part of the CaSO₄ formed in the center of the reaction zone is recycled by an internal screw conveyor to the end of the rotating kiln.

A Du Pont process [8 to 10] uses a continuous countercurrent reactor with heat generated internally from the reaction of SO_3 and steam, as shown in **Fig. 2**, p. 8. The interior of the reactor is divided into a reaction zone and a vaporization zone. The CaF_2 is fed continuously into the reactor by the screw conveyor. Steam and SO_3 vapor (effectively \approx 98 to 99% H_2SO_4) enters the reactor in the vaporization zone. Liquid 98 to 100% H_2SO_4 vaporizes in the vaporization zone as it is sprayed through nozzles. The amount of H_2SO_4 is approximately stoichiometric or 1 to 5% in excess. The temperature within the reaction zone is held between 150 to 300°C and does not exceed 335°C. HF gas containing small amounts of SiF_4 , CO_2 , SO_2 , H_2SO_4 vapor, and dust passes through a recovery train which isolates commercial grade HF (\approx 98% pure) by condensation and subsequent distillation [8 to 10].



Manufacture of hydrogen fluoride, Du Pont (U.S.A.) [5, 6].

- 1) Rotating shell. 2) Lifter blades. 3), 4) Seals. 5) Screw conveyor.
- 6) Gas input (SO₃, steam, inert gas). 7) H₂SO₄ input. 8) H₂SO₄ spraying by nozzles. 9) HF output. 10) CaSO₄ discharge.

References:

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2.1.1.2.2.1.3 Modified Processes

Some patents describe modified procedures. A sintering apparatus is fed with a 1:1 ratio of CaF_2 and concentrated H_2SO_4 together with anhydrous $CaSO_4$ in 50 to 150% excess of the amount produced by the reaction. The temperature is held below 50°C, preferably at 15 to 20°C [1], see also [2 to 4].

Some patents describe processes in which HF or a similar substance is also added. For example, if the reaction between CaF_2 and H_2SO_4 is conducted in liquid HF and the system is kept fluid, heat transfer is improved [5]. A process which involves the formation of a mobile slurry of finely divided fluorspar (99% CaF_2) and H_2SO_4 containing HF (10 wt%) or FSO₃H at 10 to 20°C is described in [6]. On feeding the slurry continuously on to preheated $CaSO_4$ (120 to 200°C), HF is evolved [6], see also [7]. A mobile slurry can also be formed with an inert liquid like 1,2,4-trichlorobenzene [8].

Some patents deal with fluidized bed processes in which CaF₂ reacts with sulfuric acid vapor or with SO₃ and water vapor. This method is interesting in respect to the better exploitation of the raw material and the improved heat transfer. One procedure involves fluidizing the solid CaSO₄ by-product and heating the fluidized bed up to 300°C with CO₂ (1.5 atm and 600°C) from burning coke in air [9]. To this fluidized bed is added a 1:1 mixture of 98% CaF₂ and 100% H₂SO₄ [9, 10], which are heated by the CaSO₄. The gas is

conducted through a condenser cooled to -70° C, which removes 99% of the HF produced [9]. A similar reactor produces HF of 98% purity [11] by mixing a preheated spray of powdered CaF₂ with a preheated spray of H₂SO₄ at 150 to 300°C. The CaSO₄ crystallizes into dry porous grains [11 to 13]. HF can be produced by the reaction of CaF₂ with gaseous H₂SO₄, steam, and air, which is the carrier gas, at 330 to 370°C in a fluidized bed, the CaF₂:H₂SO₄:H₂O molar ratio being 1:1.35:1.8. The yield of HF is 91% based on the CaF₂. This reaction is carried out so that no liquid phase appears in the reaction space. The CaSO₄ residue does not agglomerate, and no HSO₃F is formed [14], see also [15]. The manufacture of HF by the reaction of CaF₂ with SO₃ and H₂O vapor is described in [16, 17].

Finely ground CaF₂ is treated with hot H_2SO_4 , oleum, and the spent acid (initially cold acidified HF solution and cold pure HF solution) from the multistage countercurrent washing of the crude HF gas [18]. This reaction is carried out in a rotating tubular reactor [18] or three-stage reactor [19]. HF can also be produced from preheated CaF₂ (>550°C) and H_2SO_4 (80 to 110°C) in a countercurrent heat exchanger. The reaction rate can be increased by adding CaO, SO₃, and oleum [20]. A method for producing 99% HF (<0.05% H_2SO_4) by treating CaF₂ (SiO₂≈1%, CO₃²~1%) with drops of acid (HF:70%, H_2SO_4) by treating fluorspar with 92.5% H_2SO_4 in the presence of an oxidizing agent, such as H_2O_2 (0.05 to 0.1 wt%), which is introduced into the H_2SO_4 solution mixed with hydrofluoric acid (~0.04 wt%) [22]. Decomposing fluorspar with H_2SO_4 at 160 to 280°C, followed by thermal treatment of the reaction mass at 250 to 270°C in a current of air, produces HF [23].

 SO_3 , H_2SO_4 , and fluorspar react to form HFSO $_3$, which is then decomposed by H_2O into H_2SO_4 and HF of high purity. The gases leaving the fluorspar furnace are passed through a condenser operating at 25 to 45°C to remove substantially all of the HSO $_3$ F. To keep the hydrolysis of HSO $_3$ F under control the fluorosulfonic acid is passed through a number of hydrolysis chambers [24]. A limited amount of water is slowly added to each chamber [24]. Contamination with diluent gases including SiF_4 does not impaire the conversion from HF into HSO $_3$ F by reaction with SO_3 [25].

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2.1.1.2.2.2 Manufacture from CaF₂ without the Use of H₂SO₄

HF can be produced by the hydrothermal process $CaF_2 + SiO_2 + H_2O \xrightarrow{heat} CaSiO_3 + 2HF$ at ≈ 1925 to $2760^{\circ}C$, which gives an 80% conversion of H_2O to 90% HF. The heat is provided by an electrically augmented burner in which a hydrocarbon gas (CH₄, C₃H₈, fuel oil) is burned in air, O_2 , or oxygen-enriched air to form the steam [1].

A fluorite concentrate (CaF_2 95%; SiO_2 1 to 3%; H_2O 1%) can be treated 3 h with H_3PO_4 to give HF in a 90% yield based on the fluorine in the concentrate [2].

A molded mixture of powdered siliceous matter, CaF_2 or lower grade CaF_2 (<50%) [4], and $CaSiO_3$ is calcined at 1000 to 1300°C [3 to 5] with steam to produce HF and α -CaSiO₃ or pseudowollastonite $Ca_3[Si_3O_9]$. Even if the lower grade CaF_2 is used, the CaF_2 is >97% defluorinated [3].

HF can be produced simultaneously with Portland cement clinker [6] or NaAlO₂ [7].

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2.1.1.2.3 Manufacture from H₂SiF₆

2.1.1.2.3.1 General Remarks

H₂SiF₆ is obtained as a by-product from the acidulation and concentration steps of wet-process H₃PO₄ production and from phosphate fertilizer production. Because of the enormous supply of fluorine in phosphate rock reserves and the large amount of fluorine